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PATENT

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No.: Not yet assigned - 371 of PCT/FR00/01828  
Filing Date: Herewith  
Applicant: ASPAR, et al.  
Title: PROCESS FOR MAKING A THIN FILM BY APPLYING PRESSURE  
Attorney Docket: 2541-00011

Box PCT  
Hon. Commissioner of Patents and Trademarks  
Washington, D.C. 20231

FIRST PRELIMINARY AMENDMENT

Sir:

Applicants herewith submit this Preliminary Amendment to the application filed herewith, for consideration prior to the calculation of the filing fee, as follows:

IN THE CLAIMS

Please cancel claims 1 - 20 without prejudice and replace with new claims 21 - 40.

21. (NEW) A process for making a thin film starting from a substrate of a solid material having a plane face comprising:

the implantation of gaseous compounds in the substrate to make a layer of micro-cavities at a depth from the plane face corresponding to the thickness of the required thin film, the gaseous compounds being implanted under conditions that could weaken the substrate at the layer of micro-cavities; and